

REMARKS/ARGUMENTS

Favorable reconsideration of this application is requested in view of the amendments above and the remarks which follow.

Disposition of Claims

Claims 1-25 are pending in this application. Claims 10-25 are withdrawn from consideration due to a restriction requirement.

Restriction and Election of Species

A. *Restriction requirement between distinct inventions*

The Examiner requires restriction to one of the following inventions:

- I: Claims 1-9 and 24, drawn to a device, classified in class 257, subclass 66.
- II: Claims 10-23 and 25, drawn to a method, classified in class 438, subclass 67.

Applicant hereby confirms election of the claims in Group I without traverse. In view of the restriction requirement, Applicant retains the right to present the claims in Group II in a divisional application.

B. *Election of Species*

For Group I, the Examiner requires election of one of the following patentably distinct species to which the claims shall be restricted if no generic claim is finally held to be allowable:

- Species 1: Claims 1-9, directed to a TFT.
 - Species 2: Claim 24, directed to a display screen.
- Applicant elects Species 1.

Rejections under 35 U.S.C. §112

Claim 3 was rejected under 35 U.S.C. §112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. In particular, “a thickness in the range from 30% to 60%,” as specified in claim 3, is indefinite. The term “thickness” in original claim 3 should be “porosity ratio.” Claim 3 has

been amended as set forth above to correct this typographical error. Withdrawal of the indefiniteness rejection of claim 3 is respectfully requested.

Rejections under 35 U.S.C. §102

Claim 1 was rejected under 35 U.S.C. §102(e) as being anticipated by Nishida et al. (U.S. Patent No. 6,602,767). This rejection is respectfully traversed.

In FIG. 2E, Nishida et al. disclose a barrier layer interposed between a supporting substrate and a polycrystalline silicon layer. The barrier layer is composed of porous *polycrystalline silicon*, which is made by anodizing a polycrystalline silicon wafer doped with boron in HF solution. In contrast, claim 1 recites a barrier layer composed of porous *silica*.

In view of the above, claim 1 is not anticipated by Nishida et al. Withdrawal of the anticipation rejection of claim 1 in view of Nishida et al. is respectfully requested.

Rejections under 35 U.S.C. §103

Claims 2-9 were rejected under 35 U.S.C. §103 as being obvious over Nishida et al. as applied to claim 1, and further in view of Fehlner et al. (U.S. Patent No. 4,915,772). This rejection is respectfully traversed.

Claims 2-9 depend from claim 1 and therefore incorporate all the limitations of claim 1. As previously discussed, Nishida et al. do not disclose or teach a barrier layer of porous silica interposed between a substrate and a polycrystalline silicon layer. Fehlner et al. also fail to overcome the deficiency in Nishida et al. Fehlner et al. disclose disposing a barrier layer made of a refractory material between a substrate and a polycrystalline silicon film. However, Fehlner et al. do not disclose or teach that this barrier layer is porous. Fehlner et al. teach placing a porous capping layer on the thin silicon film, not between the polycrystalline silicon film and the substrate.

In view of the above, claim 1 is not obvious over Nishida et al. combined with Fehlner et al. Claims 2-9, by virtue of their dependence on claim 1, are also not obvious over Nishida et al. in view of Fehlner et al. Withdrawal of the rejection of claims 2-9 is respectfully requested.

Conclusion

The rejected claims have been amended and/or shown to be allowable over the prior art. Applicant believes that this paper is fully responsive to each ground of rejection cited by the Examiner in the Office Action dated November 15, 2004, and respectfully requests that a timely Notice of Allowance be issued in this case.

Please apply any charges not covered or credits in connection with this filing to Deposit Account No. 03-3325 (ref. SP02-211).

Respectfully submitted,

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Adenike Adebisi
Adenike A. Adebisi
Reg. No. 42,254
Tel.: (281) 477-3450